

Title (en)
POLISHING PAD

Title (de)
POLIERKISSEN

Title (fr)
TAMPON DE POLISSAGE

Publication
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Application
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Abstract (en)
[origin: WO2009025748A1] The invention provides a polishing pad comprising a polishing layer having a polishing surface comprising plurality of grooves disposed into the polishing layer a measurable depth from the polishing surface, and a barrier region free of grooves, and a transparent window disposed in and surrounded by the barrier region.

IPC 8 full level
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CPC (source: EP US)
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Citation (search report)
• [XY] WO 2004009291 A1 20040129 - APPLIED MATERIALS INC [US]
• [XY] JP 2007118106 A 20070517 - TOYO TIRE & RUBBER CO
• [Y] US 2005060943 A1 20050324 - TURNER KYLE A [US], et al
• See references of WO 2009025748A1

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